

# Recipe for S1813 resist

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## Application

Substrate preparation: it is preferable to process the silicon substrate by evaporation of HMDS at 150°C for 45 sec, using the Delta RC80.

Tone	Positive
Reference	<a href="#">Shipley</a>
Spin coat	1.4 $\mu\text{m}$ @4000 RPM
Pre bake	1 min @115°C on hotplate
Sensitivity	53 mJ/cm <sup>2</sup>
Exposure time	Approx. ~5.3 sec @ 10 mW/cm <sup>2</sup>
Development	1 min in MF321
Stopping of development	30 sec in H <sub>2</sub> O

## Results

### Spin curve

